

Notice of References Cited

 Application/Control No.
 10/629,271

 Applicant(s)/Patent Under
 Reexamination
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 Examiner
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 Art Unit
 2813

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-2002/0090514	07-2002	Leroux et al.	428/406
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	V	Lodel Nitt KK Derwent Abstracted Publication No. JP2003017481A "Low dielectric constant insulating film material for semiconductor device, includes hollow microsphere element"
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
 Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.